Doc	Document ID Pages	Pages	Title	Current	Current XRef	Inventor
US 6(US 6074917 A 8	8	LPCVD oxide and RTA for top oxide of ONO film to improve reliability for flash memory devices	438/261	257/E29.129; 257/E29.165; 438/786; 438/954	Chang, Kent Kuohua et al.
US 63	JS 6376341 B1 8	ω	Optimization of thermal cycle for the formation of pocket implants	438/510	438/257; 438/258; 438/266	Kluth, George J. et al.
US 6.	US 6306777 B1 9	O	Flash memory having a treatment layer disposed between an interpoly dielectric structure and method of forming	438/763	257/639; 257/640; 257/646; 257/649; 438/758; 438/761; 438/787;	Ogle, Jr., Robert B. et al.